

ICS 29.045
CCS H 80



**NATIONAL STANDARD OF THE
PEOPLE'S REPUBLIC OF CHINA**

GB/T 24577-2009

**Test methods for analyzing organic contaminants on silicon
wafer surfaces by thermal desorption gas chromatography**

热解吸气相色谱法测定硅片表面的有机污染物

(English Translation)

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What this standard covers

This standard specifies the qualitative and quantitative methods of organic pollutants in the wafer surface. Using GC-MS or phosphorus selective detector or both adopted. This standard applies to polished silicon wafers and silicon oxide layer.

Document data

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Standards quoted by this document

ASTM D6196